IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

PATENT APPLICATION

•									
riventor(s):	Scheiberlich								
Appin. No.:	09	827,350							
	Series Code ↑	Serial No. 1	OIP						
Filed: Apri	16, 2001								
Hon. Commis	sioner of Patents		P APR 2 3 2003						
Vashington,	D.C. 20231		2003						
Sir:			TRADEMARY						
DEDLY/A MENDACHT/I ETTED									

Group Art U Examiner:

Atty. Dkt.

2851

Hung Nguyen

279263 P-0177.010-US

M# Client Ref

Appln. Title: Lithographic apparatus, device manufacturing method, and device

manufactured thereby

REPLY/AMENDMENT/LETTER

Date: April 23, 2003

This is a reply/amendment/letter in the above-identified application and includes the herewith attachment of same date and subject which is incorporated hereinto by reference and the signature below is treated as the signature to the attachment in absence of a signature thereto.

FEE REQUIREMENTS FOR CLAIMS AS AMENDED

1. Small Entity claim A. NOT made B. Withdrawn C. made herewith D. made previously For B & C See Required Separate Paper (Pat-256)	Claims remaining after amendment	Highest nu previously p		Present Extra	Large/Small Entity	Additional Fee	Fee Code Lg/Sm
2. Total Effective Claims	17	**minus	20	0	x \$18/\$9 =	+ \$0	103/203
3. Independent Claims	4	***minus	3	1	x \$84/\$42 =	+ \$84	102/202
4. If amendment enters <u>proper</u> multiple dependent claim(s) into this application for <u>first</u> time (leave <u>blank</u> if this is a <u>reissue</u> application) add + \$280/\$140 = 5. Original due Date: February 28, 2003							104/204
5. Original due Date: February 28	A LOSAN		a file a la				
6. Petition is hereby made to extend the original due date to cover the date this response is filed for which the requisite fee is attached (1 mo) \$110/\$55 = \$410/\$205 = \$410/\$205 = \$30/\$465 = (4 mos) \$1,450/\$725= (5 mos) \$1,970/\$985=							115/215 116/216 117/217 118/218 128/228
7. Enter any previous extension fee 8.	+ \$410	(1) (1) (1) (1) (1) (1) (1) (1) (1) (1)					
8. Extension I 9. If <u>Terminal Disclaimer</u> attached, <u>add</u> Rule 20(d) official fee							148/248
10. If IDS attached requires Official Fee under Rule 97 (c),							126 126
11. After-Final Request Fee per rules	+ \$750/370	+ \$0	146/246				
12. No. of additional inventions for examination per Rule 129(b) x \$750/375 ea							149/249
13. Request for Continued Examinat	+ \$0	1179/1279					
14. Petition fee for	+ \$0						
15.	\$494						
16. *If the entry in this space is less than entry 17. **If the "Highest number previously paid 18. ***If the "Hig	PLEASE CHARGE OUR DEP. ACCT						
	29827350 reby authorized to checoncerning any paper	arge any fee spe filed hereafter, a	Our (Our ecifically a and which	Deposit Account Order No. 814 uthorized hereafter, or a may be required under	168 279263 C# M# any missing or insufficient f Rules 16-18 (missing or in	sumciencies only)	now or

This CHARGE STATEMENT does not authorize charge of the issue fee until/unless an issue fee transmittal sheet is filed.

Query: Is appeal deadline now? If so, file Notice of Appeals separately.

Pillsbury Winthrop LLP Intellectual Property Group

P.O. Box 10500 By Atty: McLean, VA 22102

Sig:

Robert C. Perez

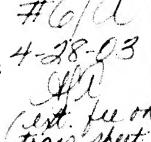
Reg. No. 39,328

Fax: (703) 905-2500 (703) 905-2159 Tel:

Atty/Sec: RP/mll

Tel: (703) 905-2000

NOTE: File this cover sheet in duplicate with PTO receipt (PAT-103A) and attachments



THE LINUTED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION OF

SCHEIBERLICH et al.

Appln. No.: 09/827,350

Filed: April 6, 2001

Confirmation No.: 2993

Group Art Unit: 2851

Examiner: H. NGUYEN

Title: LITHOGRAPHIC APPARATUS, DEVICE MANUFACTURING METHOD, AND

DEVICE MANUFACTURED THEREBY

April 23, 2003

<u>AMENDMENT</u>

Hon. Commissioner of Patents Washington, D.C. 20231

Sir: In response to the Office Action dated November 29, 2002, please amend the aboveidentified application as follows:

IN THE SPECIFICATION:

Page 9, delete the whole paragraph starting in line 6 and replace it with the following new paragraph:

The beam PB subsequently intercepts the mask MA, which is held on a mask table MT. Having traversed the mask MA, the beam PB passes through the lens PL, which focuses the beam PB onto a target portion C of the substrate W. With the aid of the second positioning means (and interferometric measuring means IF), the substrate table WT can be moved accurately, e.g., so as to position different target portions C in the path of the beam PB using wafer alignment marks P1, P2. Similarly, the first positioning means can be used to accurately position the mask MA using mask alignment marks M1, M2 with respect to the path of the beam PB, e.g., after mechanical retrieval of the mask MA from a mask library, or during a scan. In general, movement of the object tables MT, WT will be realized with the